

# ALLRESIST



*Innovation  
Creativity  
Customer Orientated Solutions*

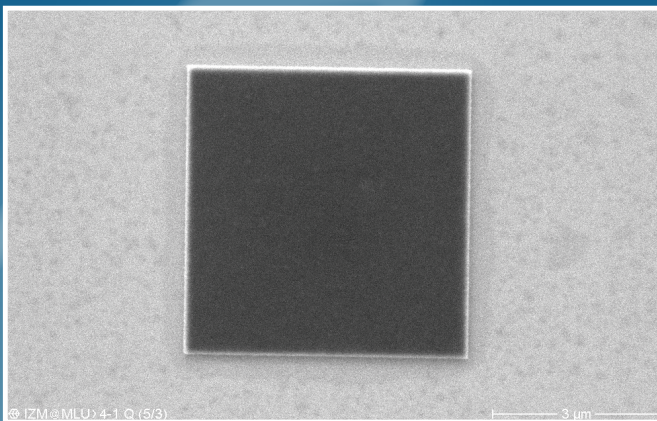
- Development, production and distribution of photo- and e-beam resists as well as process chemicals for the manufacturing of electronic components
- Wide range of products - resists for (almost) all standard technologies
- Customised versions of process-specific resists according to our customer's requests - unique selling proposition
- Particular focus on industrial research, project development in cooperation with research institutes and companies
- Individual, competent product- and technology consulting
- Short delivery times (in stock products immediately, express delivery possible)
- Customer-oriented package sizes of 250 ml, test samples of 30 ml, or more

Innovative development:

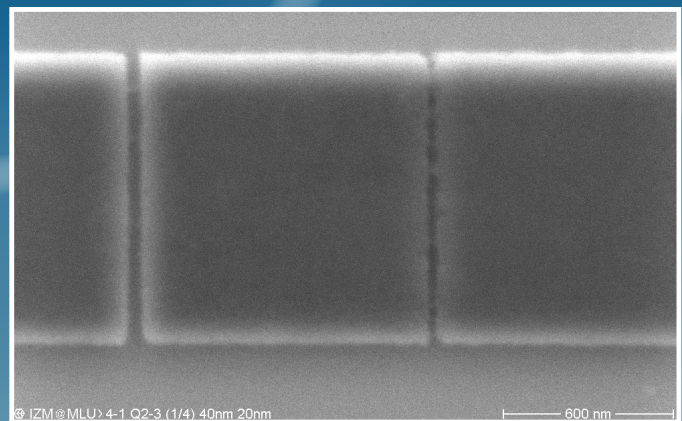
## E-beam resist **AR-N 7520 new**

high-resolution & sensitive -  
a big step to the 32nm technology

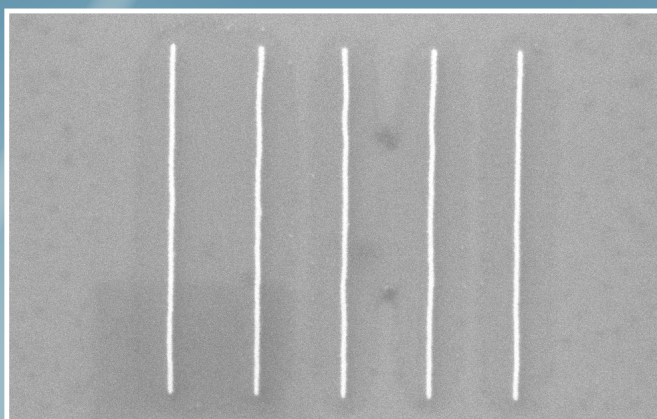
high resolution up to 35 nm, short writing times, area dose: 33  $\mu\text{C}/\text{cm}^2$ , acceleration voltage: 30 kV



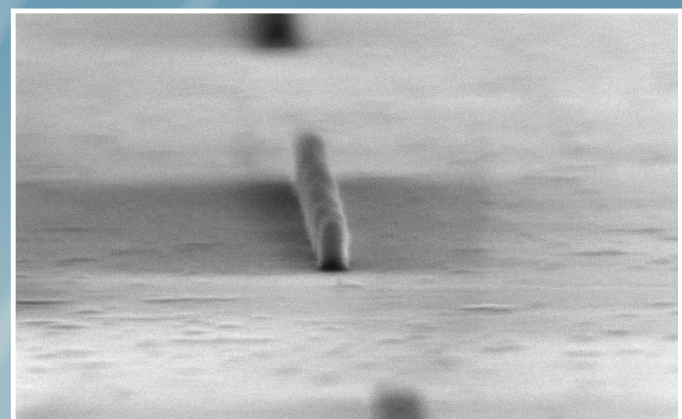
area dose: 33  $\mu\text{C}/\text{cm}^2$



30 nm trench (right), dose: 41  $\mu\text{C}/\text{cm}^2$



linewidth: 35 nm, dose: 163  $\mu\text{C}/\text{cm}^2$



LUDWIG ERHARD PREIS

2012  
Preisträger

